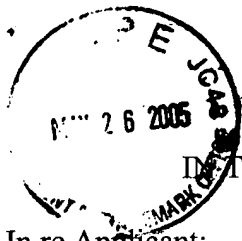


DFW



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Applicant:

Robert P. Meagley et al.

Serial No.: 10/688,521

Filed: October 17, 2003

For: Reducing Photoresist Line Edge
Roughness Using Chemically-
Assisted Reflow

§
§
§
§
§
§
§
§
§

Art Unit: 1752

Examiner: Amanda C. Walke

Docket: ITL.1026US
P16713

Assignee: Intel Corporation

Mail Stop **Amendment**
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

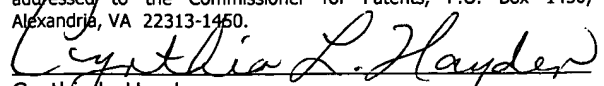
REPLY TO PAPER NO. 382005

Sir:

In response to the office action mailed March 21, 2005, reconsideration is requested in view of the following remarks.

Date of Deposit: May 24, 2005

I hereby certify under 37 CFR 1.8(a) that this correspondence is being deposited with the United States Postal Service as **first class mail** with sufficient postage on the date indicated above and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.


Cynthia L. Hayden